

MICROFABRICATION

Resist Track system

Manufacturer: SÜSS MicroTec

Model: RCD8 COATER+
VP8+HP8BM+RCD8 DEVELOPER



General Description:

The Resist Track System is a semi-automatic cluster tool equipment for photoresist patterning of wafers up to 200 mm diameter. It includes an HMDS adhesion vapor primer system (VP8), a photoresist spin coating system (RCD8 coater), a photoresist baking hot plate (HP8) and a puddle photoresist development system (RCD8 developer).

Key Specifications:

- Substrates from 2" up to 8"
- Up to 3 different resist lines for semi-automatic dispense
- Syringe dispensing
- GYRSET® technology
- Hotplate module up to 250°C
- HMDS Primer module up to 125°C

Availability	Use allowed for all researchers with permission
Location	Cleanroom C5 Europastraße 12 9524 Villach
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